L Number	Hits	Search Text	DB	Time stamp
-	5301148	aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:38
-	922075	oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:37
-	5381543	anneal$4 or heat$4 or treat$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 14:35
-	9119385	oxygen or "o.sub.2" or "o" or hydrogen or "h.sub.2" or "h" or fluorine or "f.sub.2" or "f" or halogen	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 14:39
-	7278429	sidewall or wall or side or spacer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:39
-	102865	(aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with ((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4)) with (oxygen or "o.sub.2" or "o" or hydrogen or "h.sub.2" or "h" or fluorine or "f.sub.2" or "f" or halogen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:04
-	263608	(aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (sidewall or wall or side or spacer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 14:57
-	4456020	opening or hole or aperture	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 17:41
-	17342	((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with ((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4)) with (oxygen or "o.sub.2" or "o" or hydrogen or "h.sub.2" or "h" or fluorine or "f.sub.2" or "f" or halogen)) and ((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (sidewall or wall or side or spacer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 14:58
-	39624	(aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (remov$4 or etch$4) with (opening or hole or aperture)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:05

-	2868	(((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with ((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4)) with (oxygen or "o.sub.2" or "o" or hydrogen or "h.sub.2" or "h" or fluorine or "f.sub.2" or "f" or halogen)) and ((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (sidewall or wall or side or spacer))) and ((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (remov$4 or etch$4) with (opening or hole or aperture))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:04
-	146646	contact adj4 (opening or hole or aperture)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 17:43
-	10597	(aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (remov$4 or etch$4) with (contact adj4 (opening or hole or aperture))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:07
-	1036	(((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with ((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4)) with (oxygen or "o.sub.2" or "o" or hydrogen or "h.sub.2" or "h" or fluorine or "f.sub.2" or "f" or halogen)) and ((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (sidewall or wall or side or spacer))) and ((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (remov$4 or etch$4) with (contact adj4 (opening or hole or aperture)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:24
-	2002512	aluminum oxide or "al.sub.2 o.sub.3" or "al.sub.2o.sub.3"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:26
-	1662540	oxide or dioxide or "sio" or "sio.sub.2" or nitride or "si.sub.3 n.sub.4" or "si.sub.3n.sub.4"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:28
-	31880	copper near2 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:28
-	2272440	(aluminum oxide or "al.sub.2 o.sub.3" or "al.sub.2o.sub.3") or (oxide or dioxide or "sio" or "sio.sub.2" or nitride or "si.sub.3 n.sub.4" or "si.sub.3n.sub.4") or (copper near2 oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:31

-	132644	(insulating or insulator or ((aluminum oxide or "al.sub.2 o.sub.3" or "al.sub.2o.sub.3") or (oxide or dioxide or "sio" or "sio.sub.2" or nitride or "si.sub.3 n.sub.4" or "si.sub.3n.sub.4") or (copper near2 oxide))) with (sidewall or wall or side or spacer) with (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:39
-	2938	((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with ((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4)) with (oxygen or "o.sub.2" or "o" or hydrogen or "h.sub.2" or "h" or fluorine or "f.sub.2" or "f" or halogen)) same ((insulating or insulator or ((aluminum oxide or "al.sub.2 o.sub.3" or "al.sub.2o.sub.3") or (oxide or dioxide or "sio" or "sio.sub.2" or nitride or "si.sub.3 n.sub.4" or "si.sub.3n.sub.4") or (copper near2 oxide))) with (sidewall or wall or side or spacer) with (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 15:39
-	225	(((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with ((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4)) with (oxygen or "o.sub.2" or "o" or hydrogen or "h.sub.2" or "h" or fluorine or "f.sub.2" or "f" or halogen)) same ((insulating or insulator or ((aluminum oxide or "al.sub.2 o.sub.3" or "al.sub.2o.sub.3") or (oxide or dioxide or "sio" or "sio.sub.2" or nitride or "si.sub.3 n.sub.4" or "si.sub.3n.sub.4") or (copper near2 oxide))) with (sidewall or wall or side or spacer) with (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon))))) and ((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (remov$4 or etch$4) with (contact adj4 (opening or hole or aperture)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 16:11
-	552	438/666.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 16:17
-	27455	patterned adj3 (conductor or conductive or metal or (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 16:20
-	2396779	transform$4 or convert$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/02 16:20

-	7255255	(oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4) or (transform$4 or convert$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 16:24
-	2477	((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4) or (transform$4 or convert$4)) with (patterned adj3 (conductor or conductive or metal or (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 16:25
-	559	(((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) or (anneal$4 or heat$4 or treat$4) or (transform$4 or convert$4)) with (patterned adj3 (conductor or conductive or metal or (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon))))) and (contact adj4 (opening or hole or aperture))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/02 16:26
-	190	438/635.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 15:02
-	1984	438/637.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 15:04
-	28716	submicron or sublithograph$8 or submi?cron or sub?lithograph$8	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 17:41
-	6152289	opening or hole or aperture or via	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 17:42
-	1092	(submicron or sublithograph$8 or submi?cron or sub?lithograph$8) near5 (opening or hole or aperture or via)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 17:42
-	559	(submicron or sublithograph$8 or submi?cron or sub?lithograph$8) near4 (via or (contact adj2 (opening or hole or aperture)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 17:45
-	7981879	sidewall or wall or side or spacer or edge	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 17:46
-	408	((submicron or sublithograph$8 or submi?cron or sub?lithograph$8) near4 (via or (contact adj2 (opening or hole or aperture)))) and (sidewall or wall or side or spacer or edge)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/03 17:47
-	1	6441430.pn.	USPAT	2004/09/06 14:18
-	2	6441430.pn.	USPAT; US-PGPUB; EPO; DERWENT	2004/09/06 14:18

-	918	438/95.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 14:20
-	3056117	oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4 or transform$4 or convert$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 14:22
-	214	438/95.ccls. and (oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4 or transform$4 or convert$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 14:22
-	727	438/595.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:16
-	4171	dummy near6 gate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:17
-	34	438/595.ccls. and (dummy near6 gate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:36
-	2255	dummy adj3 gate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:36
-	922520	oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:37
-	5307156	aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:38
-	270947	(oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) same (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:39
-	589	(dummy adj3 gate) and ((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) same (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:39
-	7284121	sidewall or wall or side or spacer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:40
-	555	((dummy adj3 gate) and ((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) same (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)))) and (sidewall or wall or side or spacer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:40

-	187590	(oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) with (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:41
-	508	((oxidi$5 or oxidat$4 or nitridi$4 or nitridat$4 or nitrided or hydrogenat$4 or fluorinat$4) with (aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon))) and (dummy adj3 gate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:44
-	1900986	wire or interconnect$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:46
-	68225	dummy	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:47
-	358	(aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (wire or interconnect$4) with dummy	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:47
-	2635131	contact adj3 (opening or hole or aperture) or via	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:48
-	193	((aluminum or al or copper or cu or silicon or si or polysi or polysilicon or (poly or polycrystal$4) adj2 (si or silicon)) with (wire or interconnect$4) with dummy) and (contact adj3 (opening or hole or aperture) or via)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/06 15:49